



ADVANCED RESEARCH CENTER FOR NANOLITHOGRAPHY

## SOURCE

*Oscar Versolato*

## EUV Plasma Processes

*Oscar Versolato*

## Plasma Theory & Modeling

*John Sheil*

## Ions Interaction

*Ronnie Hoekstra*

## METROLOGY

*Stefan Witte*

## EUV Generation & Imaging

*Stefan Witte &  
Kjeld Eikema*

## Light-Matter Interaction

*Paul Planken*

## Computational Imaging

*Arie den Boef*

## High-Harmonic Generation and EUV Science

*Peter Kraus*

## Nanoscale Imaging & Metrology

*Lyuba Amitonova*

## MATERIALS

*R. Bliem a.i.*

## Materials & Surface Science for EUV Lithography

*Roland Bliem*

## Contact Dynamics

*Steve Franklin &  
Bart Weber*

## Materials Theory & Modeling

*Emilia Olsson*

## INTEGRATION

*Wim van der Zande a.i. (ARCNL), Marjan Fretz (ARCNL), Maarten Voncken (ASML)*